



2016 International Workshop on EUV Lithography (2016 EUVL Workshop)

June 13-16, 2016, The Center for X-ray Optics (CXRO), Lawrence
Berkeley National Laboratory, Berkeley, CA, USA

FIRST CALL FOR PAPERS

We are inviting presentations and poster papers for the 2016 International Workshop on EUV Lithography, to be held June 13-16, 2016 at The Center for X-ray Optics (CXRO) at Lawrence Berkeley National Laboratory in Berkeley, CA. This workshop, now in its ninth year, is focused on the fundamental science of EUV Lithography (EUVL). A smaller group setting suitable for networking and brainstorming, with a focus on fundamentals, sets this conference apart from other larger conferences based on the commercial aspects of EUVL.

Technology review papers and presentations with innovative approaches to current EUV Lithography-related technical challenges are encouraged. EUV Lithography-related topics covered under this workshop include source for high volume manufacturing (HVM) and metrology, FEL based sources for EUVL, exposure tools, masks, optics, resist, contamination, metrology, patterning and cost of ownership. Papers on combinations of EUVL with multiple patterning, manufacturing readiness of EUVL and directed self-assembly (DSA) are also welcome.

The workshop will be preceded by an EUV Lithography Short Course on June 13. Registration for the workshop begins on June 14, followed by presentations, panel discussions and a poster session on June 15 and 16. The keynote speakers for the 2016 workshop will be announced soon on our website www.euvlitho.com. The 2016 International Workshop on EUV Lithography is co-organized by EUV Litho, Inc. and The Center for X-ray Optics (CXRO) at Lawrence Berkeley National Laboratory, Berkeley, CA.

Instructions for Submissions and Deadlines

Please submit abstracts of less than 200 words and indicate whether an oral or poster paper is preferred. Please also include each author's full name, e-mail address, affiliation and mailing address, together with a brief biography and photograph for the presenting author. Abstracts should be submitted via email to abstracts@euvlitho.com. The deadline for abstract submission is March 18, 2016. Authors will be notified by March 28 or earlier if their abstracts have been accepted for an oral or poster paper. For logistics related issues please contact Meeting Services at info@euvlitho.com and for technical questions, please contact Vivek Bakshi at vivek.bakshi@euvlitho.com or Patrick Naulleau at pnaulleau@lbl.gov.

Co-Organized by

